## SILICON-CONTAINING POLYMER, PROCESS FOR ITS PRODUCTION, RESIST COMPOSITION EMPLOYING IT, PATTERN-FORMING METHOD AND ELECTRONIC DEVICE FABRICATION METHOD

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## ABSTRACT OF THE DISCLOSURE

A silicon-containing polymer having a 10 tetrafunctional siloxane portion as the basic skeleton, and containing a carboxylic acid group-containing triorganosiloxane portion and a carboxylic acid derivative group-containing triorganosiloxane portion in a specific proportion. It may be advantageously used as 15 a negative non-chemical amplification resist polymer or a positive chemical amplification resist polymer.